

Growth and Nitridation of Fe thin films on (0001) Al₂O₃ substrates

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Due to of its large saturation magnetization and possible large coercivity, Fe₁₆N₂ has been believed as a promising candidate material in the next-generation rare-earth-free permanent magnet applications. However, stabilization of this meta-stable phase has long been challenged. In this work, synthesis and nitridation of (110) Fe thin films on Al₂O₃ (0001) substrates were performed by RF magnetron sputtering and in-situ and ex-situ nitridation processes. From high resolution x-ray diffraction, we confirmed (110) epitaxial Fe thin films are successfully grown. We systematically studied magnetism and microstructures from vibrating sample magnetometer, scanning electron microscope, and atomic force microscope. In addition, we will show our on-going efforts to form Fe₁₆N₂ thin films from in-situ and ex-situ nitridation processes.

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